

Form PTO-1449

U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE

LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)

ATTY. DOCKET NO. MI22-1904

PRIORITY SERIAL NO. 09/843,116

APPLICANT Michael Nuttall et al.

PRIORITY FILING DATE April 24, 2001

PRIORITY GROUP

Number					U.S. PATENT DOCUMENTS		2015		poo
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AD 5.110,757 05/1992 Arst et al. 438 489 AE 5.124,276 06/1992 Samata et al. 438 607 AF 5.364,815 11/1994 Orada 488 489 AG 5.441,012 08/1995 Abetagawa et al. 117 86 AH 5.006,911 04/1991 Sivan 357 23.11 AI 5.818,100 10/1998 Grider et al. 257 616 AJ 5.037,775 08/1991 Reisman 437 89 AK 5.646,073 07/1997 Grider et al. 437 233 FOREIGN PATEN/DOCUMENTS Document Number Date Country Class Subcla AM AN		AB	4,963,506	10/1990	Liaw et al.	438	482		
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AR Violette, Kathorine E., et al., "Low Temperature Selective Silicon Epitaxy by Ultra High Vacuum Rapid Thermal Chem Si ₂ H ₆ , H ₂ and Cl ₂ ", Appl. Phys. Lett., Vol. 68(1), pp. 66-68 (January 1996). AS Volf, Stanley, et al., "Chemical Vapor Deposition of Amorphous and Polycrystalline Films, Silicon Processing for the Vacuum Rapid Thermal Chem Si ₂ H ₆ , H ₂ and Cl ₂ ", Appl. Phys. Lett., Vol. 68(1), pp. 66-68 (January 1996).						1		<u> </u>	
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		LIST OF ART CITED (Use several sheets		APPLICANT	APPLICANT Michael Nuttall et al.						
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	AC	4,966,868	10/1990	Murali et al.		437	193				
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ATTY. DOCKET NO. MI22-1904

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